

IN THE CLAIMS

1 - 15. (Canceled)

16. (Currently Amended) A method of manufacturing an electron source comprising steps of:

exposing a surface of a substrate to a sealed atmosphere, on which surface a plurality of electron-emitting devices are to be formed, wherein the sealed atmosphere is formed by a chamber; [[and]]

introducing a gas containing carbon into the sealed atmosphere[[,]];

depositing carbon on an electro-conductive member disposed on the surface of the substrate; and

exhausting the gas containing carbon introduced into the sealed atmosphere during heating of the chamber, after the depositing of the carbon,

~~wherein the sealed atmosphere is formed by a chamber~~ and the chamber is heated before said introducing step, and

wherein the introducing of [[a]] the gas containing carbon is performed while exhausting the sealed atmosphere formed by the chamber.

17. (Currently Amended) A method of manufacturing an electron source comprising steps of:

exposing a surface of a substrate to a sealed atmosphere, on which surface a plurality of electron-emitting devices are to be formed, wherein the sealed atmosphere is formed by a chamber; [[and]]

introducing a gas containing carbon into the sealed atmosphere[[,]]; depositing carbon on an electro-conductive member disposed on the surface of the substrate; and

exhausting the gas containing carbon introduced into the sealed atmosphere during heating of the chamber, after the depositing of the carbon,

wherein ~~the sealed atmosphere is formed by a chamber~~ and the chamber is heated before said introducing step, to reduce moisture absorbed to a surface of the chamber, and

wherein the introducing of [[a]] the gas containing carbon is performed while exhausting the sealed atmosphere formed by the chamber.

18. (Currently Amended) A method of manufacturing an electron source comprising steps of:

exposing a surface of a substrate to a sealed atmosphere, wherein an electron-emitting region is to be formed [[is disposed]] on the surface of the substrate, and wherein the sealed atmosphere is formed by a chamber; [[and]]

introducing a gas containing carbon into the sealed atmosphere[,];

depositing carbon on an electro-conductive member disposed on the surface of the substrate; and

exhausting the gas containing carbon introduced into the sealed atmosphere during heating of the chamber, after the depositing of the carbon,

~~wherein the sealed atmosphere is formed by a chamber and the chamber is heated before said introducing step, and~~

wherein the introducing of ~~[[a]]~~ the gas containing carbon is performed while exhausting the sealed atmosphere formed by the chamber.

19. (Currently Amended) The method according to Claim 18, further comprising the step of applying a voltage to ~~[[an]]~~ the electro-conductive member, the electroconductive member being disposed on the surface of the substrate.

20. (Currently Amended) A method of manufacturing an electron source comprising steps of:

exposing a surface of a substrate to a sealed atmosphere, wherein an electro-conductive member, in which an electron-emitting region is to be formed, is disposed on the surface of the substrate, and wherein the sealed atmosphere is formed by a chamber; [[and]]

introducing a gas containing carbon into the sealed atmosphere[[,]]; depositing carbon on the electro-conductive member disposed on the surface of the substrate; and

exhausting the gas containing carbon introduced into the sealed atmosphere during heating of the chamber, after the depositing of the carbon,

wherein ~~the sealed atmosphere is formed by a chamber and~~ the chamber is heated before said introducing step, to reduce moisture absorbed to a surface of the chamber, and

wherein the introducing of [[a]] the gas containing carbon is performed while exhausting the sealed atmosphere formed by the chamber.

21. (Previously Presented) The method according to Claim 20, further comprising the step of applying a voltage to the electro-conductive member.

22. (Currently Amended) A method of manufacturing an electron source comprising steps of:

exposing a surface of a substrate to a sealed atmosphere, wherein an electro-conductive member, capable of being subjected to an activation of an electron-emitting function, is disposed on the surface of the substrate, wherein the sealed atmosphere is formed by a chamber; [[and]]

introducing a gas containing carbon into the sealed atmosphere[[,]];

depositing carbon on the electro-conductive member disposed on the surface of the substrate; and

exhausting the gas containing carbon introduced into the sealed atmosphere during heating of the chamber, after the depositing of the carbon,

wherein the ~~sealed atmosphere is formed by a chamber and the~~ chamber is heated before said introducing step, and

wherein the introducing of ~~[[a]]~~ the gas containing carbon is performed while exhausting the sealed atmosphere formed by the chamber.

23. (Previously Presented) The method according to Claim 22, further comprising the step of applying a voltage to the electro-conductive member.

24. and 25. (Canceled)